

INFORMATION DISCLOSURE CITATION
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Docket Number (Optional)

2003US312

Application Number

10/734,022

Applicant(s)

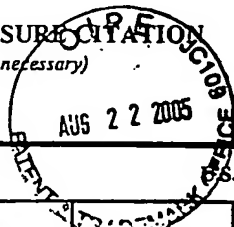
M. Dalil RAHMAN

Filing Date

December 11, 2003

Group Art Unit

1752



U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
JR		4,491,628	6/1/1985	Ito et al.			
		5,350,660	9/27/1994	Urano et al.			
		5,843,624	12/1/1998	Houlihan et al.			
		6,477,980	9/10/2002	Rahman et al.			
		6,274,286	8/14/2001	Hatakeyama et al.			

U.S. PATENT APPLICATION PUBLICATIONS

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE

FOREIGN PATENT DOCUMENTS

	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO
JR		EP 1 215 193 B1	11/17/2004	EUROPE				

OTHER DOCUMENTS

(Including Author, Title, Date, Pertinent Pages, Etc.)

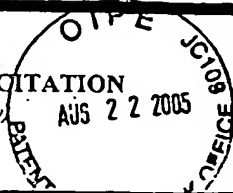
JR		Nakano et al., "Adhesion Characteristics of Alicyclic Polymers for use in ArF Excimer Laser Lithography, Proc. SPIE Vol. 3333, pp. 43 - pp. 52 (1998)
JR		Wallow et al., "Reactive ion etching of 193 nm resist candidates: current platforms, future requirements", Proc. SPIE Vol. 3333, pp. 92 - pp. 101 (1998)

EXAMINER	J Ch	DATE CONSIDERED	10/2005
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Jung et al., "Design of cycloolefin-maleic anhydride resist for ArF lithography",
SPIE Vol. 3333, pp. 11 - pp. 25 (1998)

Nozaki et al., "A novel polymer for 193-nm resist", Journal of Photopolymer Science and Technology",
Vol. 9, No. 3, pp. 509 - pp. 522 (1996)

Nozaki et al., "Evaluation of alicyclic Methacrylate Resist with a γ -Butyrolactone protective Group
for 193-nm Lithography", Journal of Photopolymer Science and Technology, Vol. 11, No. 3,
pp. 493 - pp. 498 (1998)

Tran et al., "Metal-Catalyzed Vinyl Addition Polymers for 157 nm Resist Applications.
2. Fluorinated Norbornenes: Synthesis, Polymerization, and Initial Imaging Results",
Macromolecules, Vol. 35, No. 17, pp. 6539 - pp. 6549 (2002)

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